

3600.5825
January 15, 2003 (11:54am)

Docket: AM-5825

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: Diana Xiaobing MA

Attorneys Docket: AM-5825

Serial No.: 09/922,980

Art Unit No.: 2825

Filed: August 6, 2001

Examiner: R. Rocchegiani

For: "INTEGRATED SYSTEM FOR OXIDE ETCHING AND METAL LINER
DEPOSITION"

Commissioner of Patents
Washington, DC 20231

FAX RECEIVED

JAN 15 2003

AMENDMENT UNDER 37 CFR §1.111

TECHNOLOGY CENTER 2800

Sir:

In response to the Office Action of November 7, 2002, please amend the above
application as follows:

In the claims:

1. (Twice Amended) An integrated etch and metal liner process of a substrate including a dielectric layer and covered with a patterned mask material, comprising the steps of:
transferring the substrate into a first transfer chamber held at a first pressure below atmospheric pressure;
transferring the substrate from the first transfer chamber to an etching chamber and etching according to said patterned mask material through said dielectric layer to an etch stop layer to form a hole in said oxide layer;
ashing said mask material;

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